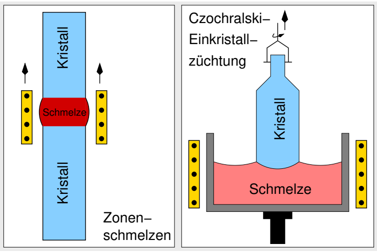
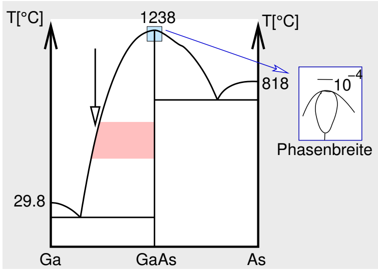
3. Herstellung von Halbleitern

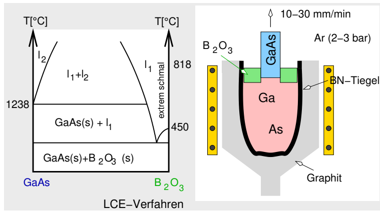
3.1. Substratherstellung



Kristallzüchtung

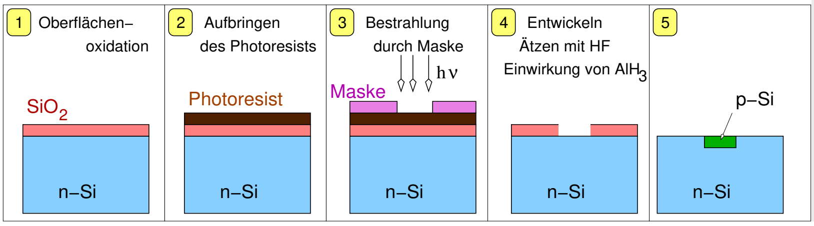


PD GaAs

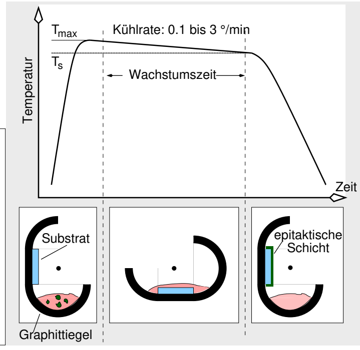


LEC-Verfahren

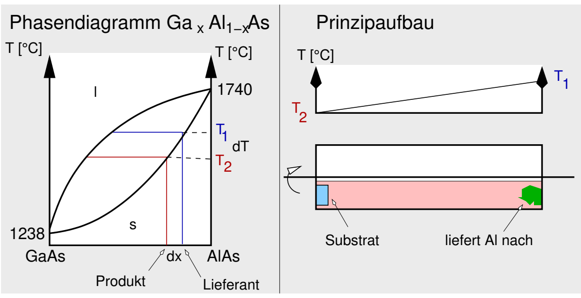
3.2. Depositionsverfahren/Herstellung epitaktischer Materialien



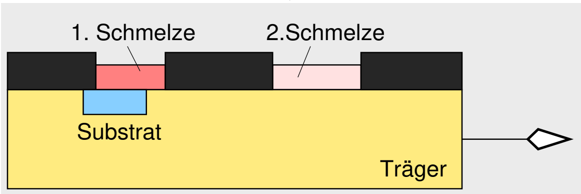
Diffusionsverfahren



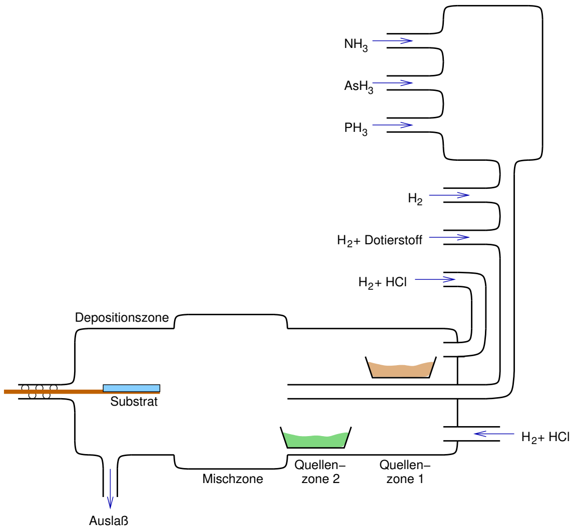
LPE II: Tipping



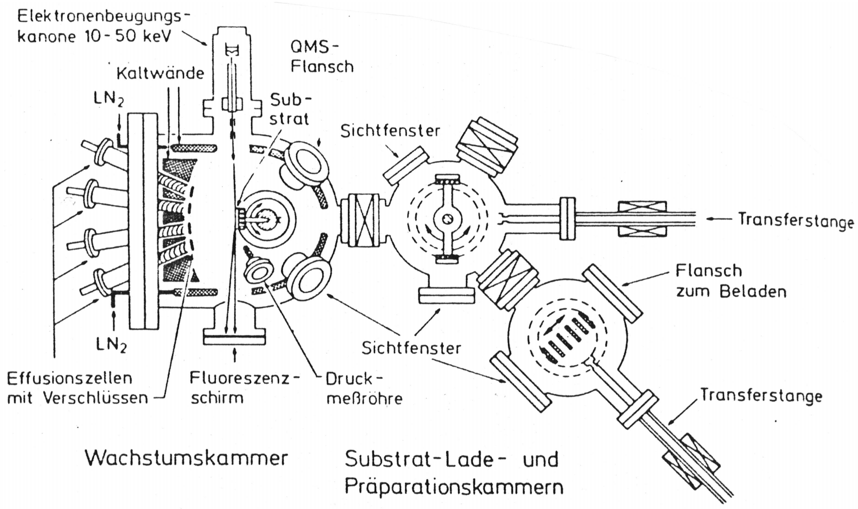
LPE III: Steady-State-Technik



LPE IV: Sliding



Chemical Vapor Deposition (CVD)



Molekularstrahl-Epitaxie (MBE)